ABSTRACT

Lithographic Apparatus, Device Manufacturing Method
and Computer Program Product

In a lithographic apparatus, a corrective irradiation procedure is performed using an illumination mode arranged so as to heat a selected part of an element of the projection system near a pupil plane thereof that is relatively unheated during production exposure. The corrective irradiation procedure aims to improve uniformity of optical element heating of the projective system and/or to reduce a phase gradient.

[Figure 3]